	Hits	Search Text	DB	Time stamp
umber			USPAT;	2002/12/17
	78	117/9.ccls. and amorphous same (silicon	US-PGPUB;	15:19
		or germanium or si or ge or sige)	EPO; JPO;	i
			DERWENT;	
			IBM TDB	
ļ			USPAT;	2002/12/17
	52	117/9.ccls. and amorphous same (silicon	US-PGPUB;	15:28
		or germanium or si or ge or sige) same	EPO; JPO;	
		(heat adj treat\$4 or rapid adj thermal or	DERWENT;	
		rta or rtp or ptp or anneal\$4 or laser)	IBM TDB	
			USPAT;	2002/12/17
_	8	117/9.ccls. and amorphous same (germanium or ge or sige) same (heat adj treat\$4 or	US-PGPUB;	15:43
		rapid adj thermal or rta or rtp or ptp or	EPO; JPO;	
		anneal\$4 or laser)	DERWENT;	
		anneal \$4 of lasel	IBM_TDB	
		117/4-9.ccls. and amorphous same	USPAT;	2002/12/17
-	24	(germanium or ge or sige) same (heat adj	US-PGPUB;	15:56
		treat\$4 or rapid adj thermal or rta or	EPO; JPO;	
		rtp or ptp or anneal\$4 or laser)	DERWENT;	
		i -	IBM_TDB	
	10	(117/4-9.ccls. and amorphous near4	USPAT;	2002/12/17
-	42	(rilicon or si) same (heat add treats4 or	US-PGPUB;	16:08
		I would add thermal or rta or IID of PLP Of	EFO, OFO,	
		anneal\$4 or laser)) and (ge or germanium)	DEVARIATION	
	1		IBM_TDB	2000/10/17
-	24	(117/4-9.ccls. and amorphous near4	USPAT;	2002/12/17
	24	(silicon or si) same (laser)) and (ge or	US-PGPUB;	16:48
		germanium)	EPO; JPO;	
	1	german and	DERWENT;	
			IBM_TDB	2002/12/17
-	1	((amorphous near3 (silicon or si) and	USPAT;	2002/12/17
	1	l neboug near3 (dermanium of de oi	US-PGPUB;	17:56
	1	sige)) same (anneal\$4 or laser) and TFT)	EPO; JPO;	
		and 117/\$4.ccls.	DERWENT;	
			IBM_TDB	2002/12/18
-	9	(ge or germanium or sige or silicon adj	USPAT;	11:23
	1	germanium) same second near3 amorphous	US-PGPUB; EPO; JPO;	11.23
		near2 layer and TFT	DERWENT;	
			IBM TDB	
			USPAT;	2002/12/18
_	43	crystal\$4 same second near3 amorphous	US-PGPUB;	11:55
		near2 layer and TFT	EPO; JPO;	
			DERWENT;	
			IBM TDB	
		1 2 -mannhaug	USPAT;	2002/12/18
-	2	crystal\$4 same second near3 amorphous	US-PGPUB;	13:16
		near2 layer and TFT and Ilrst heal3 (ge	EPO; JPO;	
		or germanium)	DERWENT;	
			IBM TDB	
			USPAT;	2002/12/18
_		TFT and first near3 (ge or germanium)	US-PGPUB;	13:18
		same crystal\$4	EPO; JPO;	
			DERWENT;	
			IBM TDB	
_		s s + man? (go or germanium)	USPAT;	2002/12/18
		7 TFT and first near3 (ge or germanium)	US-PGPUB;	13:25
	1	same amorphous	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	_	5 electrode same insulat\$4 same amorphous	USPAT;	2002/12/18
_	2	same germanium and TFT	US-PGPUB;	I
		same germanium and ii.	EPO; JPO;	
			DERWENT;	
	1	l I	IBM TDB	1

	1-1-	TFT same anneal\$4 same laser same (xenon	USPAT;	2002/12/18
-	16	or mercury or metal adj halide)	US-PGPUB;	15:20
		or mercury or metal adj narrati	EPO; JPO;	
			DERWENT;	
			IBM TDB	
		/	USPAT;	2002/12/18
-	40	anneal\$4 same laser same (mercury or	US-PGPUB;	15:25
		metal adj halide)	EPO; JPO;	13.23
			DERWENT;	
			IBM_TDB	2002/12/19
-	39	crystal\$4 near3 improv\$3 same amorphous near5 (silicon or germanium or si or ge or sige) same TFT	USPAT;	
			US-PGPUB;	09:40
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_		crystal\$4 near3 improv\$3 same amorphous near5 (germanium or ge or sige) and TFT	USPĀT;	2002/12/18
	1		US-PGPUB;	15:49
		nears (germanium of ge of sigo, and the	EPO; JPO;	
			DERWENT;	
			IBM TDB	
		A Company i um	USPAT;	2002/12/18
_	24	crystal\$4 near3 improv\$3 same (germanium	US-PGPUB;	16:15
		or ge or sige) and TFT	EPO; JPO;	13.23
			1	
			DERWENT;	
			IBM_TDB	2002/12/18
-	110	[cyn or chemical adi vapor ad]	USPAT;	16:23
	110		US-PGPUB;	16:23
		deposit\$4) and turbo adj molecular adj	EPO; JPO;	
	1	pump\$4	DERWENT;	i
			IBM_TDB	2222 (12 (12
	10	amorphous near3 (silicon or si) same	USPAT;	2002/12/18
-	10	plasma adj (CVD or chemical adj vapor adj	US-PGPUB;	16:35
		deposit\$4) same turbo adj molecular adj	EPO; JPO;	1
		depositive) same curbo adj morosuru	DERWENT;	
		pump\$4	IBM TDB	
			USPAT;	2002/12/18
_	7	amorphous same silicon same two adj step	US-PGPUB;	16:49
		same crystal\$4 same laser and tft	EPO; JPO;	
			DERWENT;	
			IBM TDB	
			USPAT;	2002/12/19
_	10	amorphous same two adj step same	USPAL;	09:40
_		crystal\$4 same laser and tft	1	1 3.10
	1	V-1	EPO; JPO;	
			DERWENT;	\
			IBM_TDB	0000/10/10
-		second near5 anneal\$4 same laser and	USPAT;	2002/12/18
	79	crystal\$4 near5 laser and tft	US-PGPUB;	17:45
		crystato4 means raser and ser	EPO; JPO;	
			DERWENT;	
	1		IBM TDB	